超大规模集成电路基础 Fundamental of VLSI

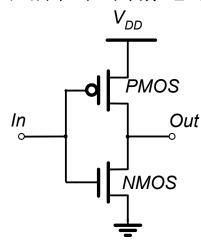
第五章 CMOS 反相器





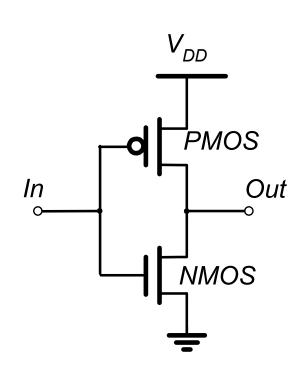


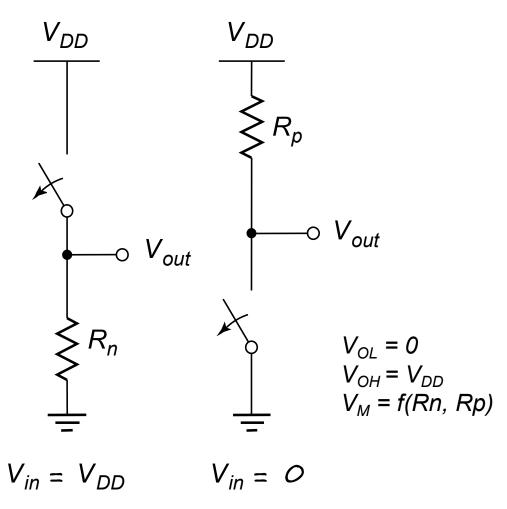
- 输出高电平和低电平分别为V_{DD}和GND
- 逻辑电平与器件的相对尺寸无关(无比逻辑),所以晶体管可采用最小尺寸
- 稳态时输出和V_{DD}或GND之间总存在一条具有有限电阻的 通路
- CMOS反相器输入电阻极高,稳态输入电流几乎为零
- CMOS在稳态情况下电源线和地线没有直接通路,没有电流存在(忽略漏电流),因此该门不消耗任何静态功率



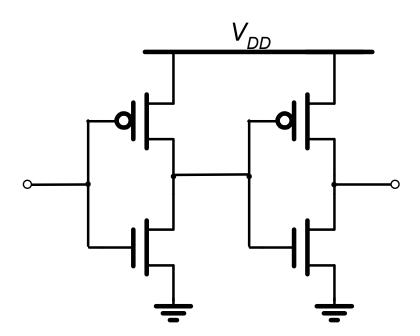
CMOS反相器

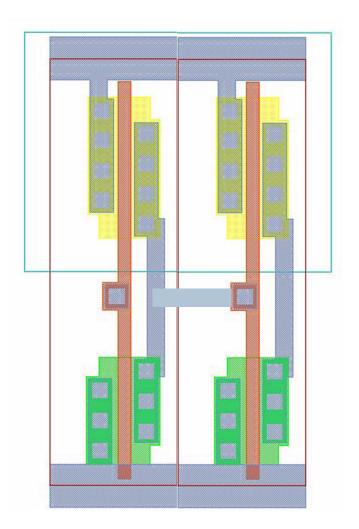






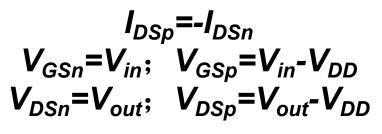
CMOS反相器

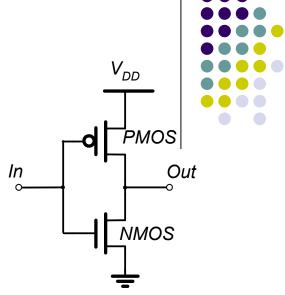


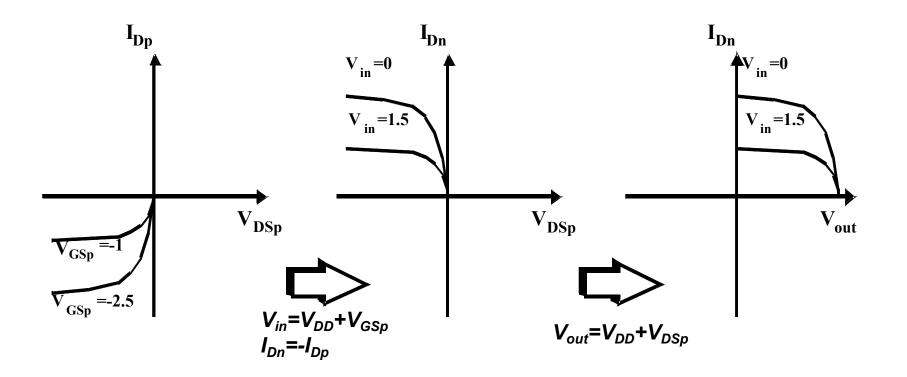




PMOS负载曲线







CMOS反相器负载曲线

$$I_{Dn}$$

$$V_{in} = 0$$

$$V_{in} = 2.5$$

PMOS

$$V_{in} = 0.5$$

$$V_{in}=2$$

$$V_{in} = 1$$

$$V_{in} = 1.5$$

$$V_{in} = 1.5$$

$$V_{in} = 1.5$$

$$V_{in} = 1$$

$$V_{in} = 1$$

$$V_{in} = 1$$

$$V_{in} = 0.5$$



$$V_{in} = 0$$



$$V_{in} = 2.5$$

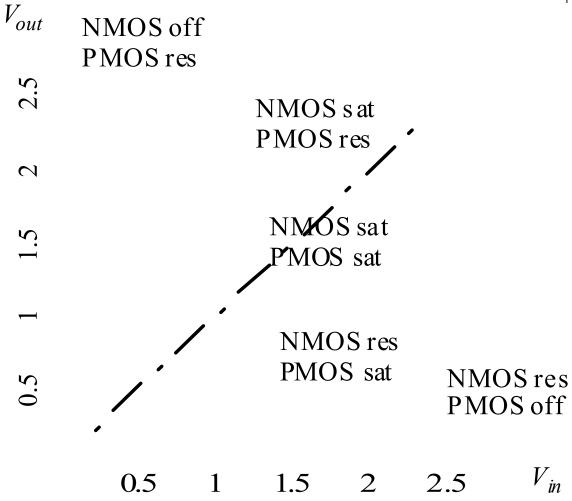
 $V_{in}=2$



静态CMOS反相器中NMOS和PMOS管的负载曲线

CMOS反相器VTC







- 开关阈值V_M=f(V_M)
- 假设电源电压足够高,器件处于速度饱和(即 $V_{DSAT} < V_{M} V_{T}$)

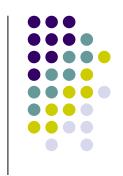
$$k_{n}V_{DSATn}\left(V_{M}-V_{Tn}-\frac{V_{DSATn}}{2}\right)+k_{p}V_{DSATp}\left(V_{M}-V_{DD}-V_{Tp}-\frac{V_{DSATp}}{2}\right)=0$$

求解VM得到:

$$V_{M} = \frac{\left(V_{Tn} + \frac{V_{DSATn}}{2}\right) + r\left(V_{DD} + V_{Tp} + \frac{V_{DSATp}}{2}\right)}{1 + r} \qquad r = \frac{k_{p}V_{DSATp}}{k_{n}V_{DSATn}} = \frac{\upsilon_{satp}W_{p}}{\upsilon_{satn}W_{n}}$$

如果 V_{DD} 很大, V_{M} 计算可进一步简化为 $V_{M} = \frac{rV_{DD}}{1+r}$

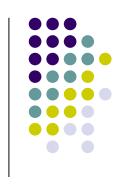




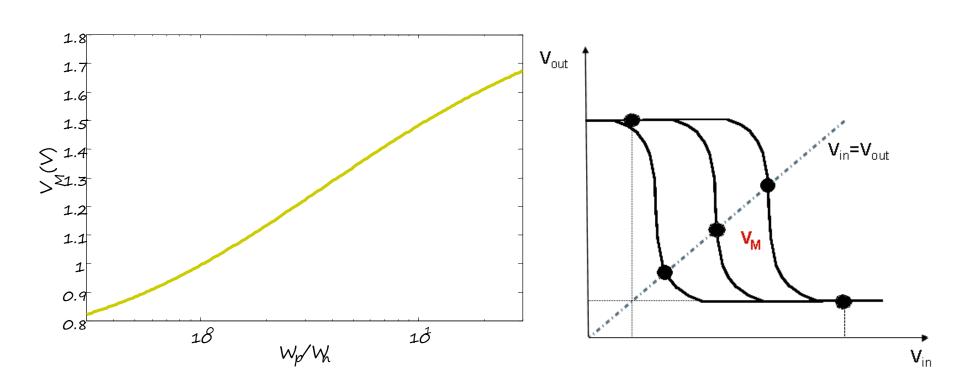
• 给定开关阈值确定PMOS和NMOS器件的尺寸

$$\frac{(W/L)_{p}}{(W/L)_{n}} = \frac{k'_{n}V_{DSATn}\left(V_{M} - V_{Tn} - \frac{V_{DSATn}}{2}\right)}{-k'_{p}V_{DSATp}\left(V_{M} - V_{DD} - V_{Tp} - \frac{V_{DSATp}}{2}\right)}$$

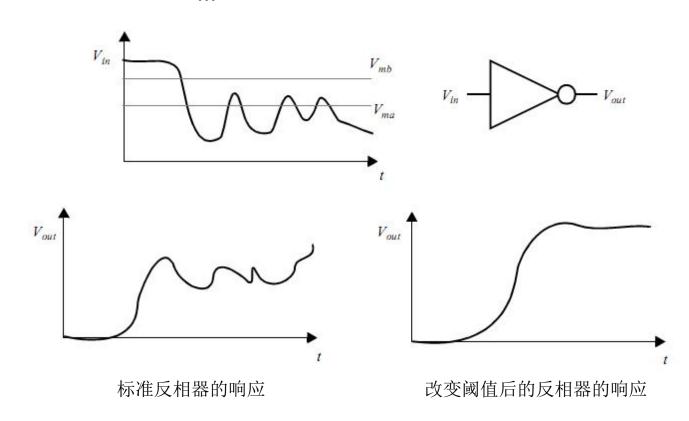




- 反相器阈值V_M具有特点
 - V_M对于器件比值的变化不敏感
 - 改变W_p/W_n的影响是使反相器的VTC过渡区平移

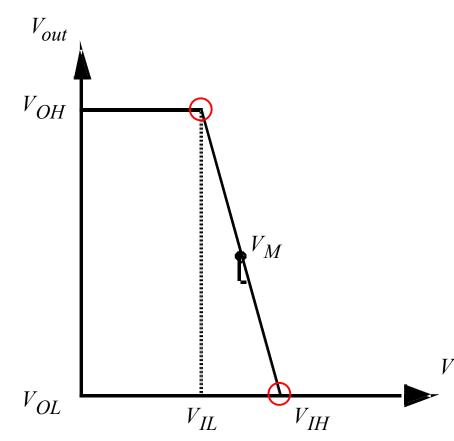


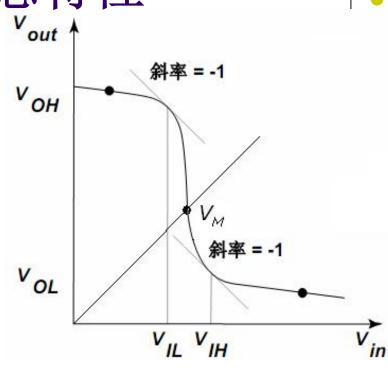
• 反相器阈值V_M调整





- 噪声容限
 - 反相器VTC线性近似





$$V_{IH} - V_{IL} = - rac{(V_{OH} - V_{OL})}{g} = rac{-V_{DD}}{g}$$
 $V_{IH} = V_M - rac{V_M}{g}$
 $V_{IL} = V_M + rac{V_{DD} - V_M}{g}$
 $NM_H = V_{DD} - V_{IH}$
 $NM_L = V_{IL}$





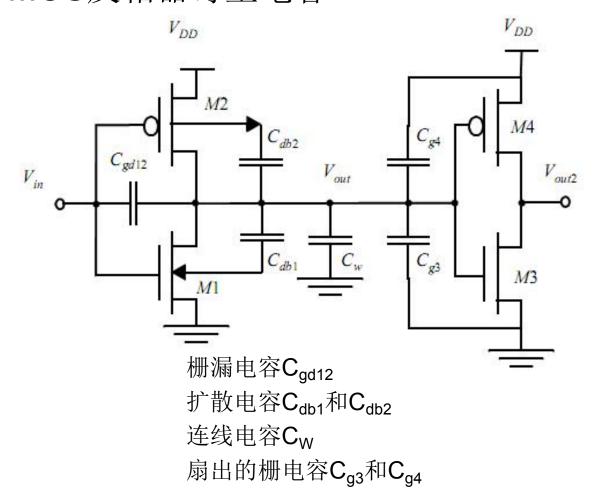
- 噪声容限
 - 反相器增益g计算

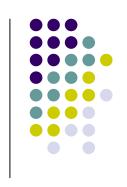
$$k_{n}V_{DSATn}\left(V_{in}-V_{Tn}-\frac{V_{DSATn}}{2}\right)(1+\lambda_{n}V_{out})+k_{p}V_{DSATp}\left(V_{in}-V_{DD}-V_{Tp}-\frac{V_{DSATp}}{2}\right)(1+\lambda_{p}V_{out}-\lambda_{p}V_{DD})=0$$

$$g = \frac{dV_{out}}{dV_{in}} = -\frac{k_{n}V_{DSATn}(1 + \lambda_{n}V_{out}) + k_{p}V_{DSATp}(1 + \lambda_{p}V_{out} - \lambda_{p}V_{DD})}{\lambda_{n}k_{n}V_{DSATn}\left(V_{in} - V_{Tn} - \frac{V_{DSATn}}{2}\right) + \lambda_{p}k_{p}V_{DSATp}\left(V_{in} - V_{DD} - V_{Tp} - \frac{V_{DSATp}}{2}\right)}$$

$$g \approx -\frac{k_n V_{DSATn} + k_p V_{DSATp}}{I_D(V_M)(\lambda_n - \lambda_p)} = \frac{1 + r}{(V_M - V_{Tn} - \frac{V_{DSATn}}{2})(\lambda_n - \lambda_p)}$$

• CMOS反相器寄生电容

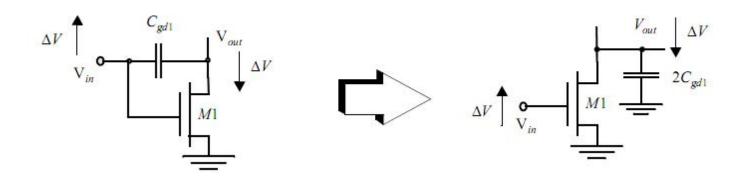








- CMOS反相器寄生电容
 - 栅漏电容Cgd12
 - $\quad \quad \mathsf{C}_{\mathsf{gd12}} = \mathsf{C}_{\mathsf{gd1}} + \mathsf{C}_{\mathsf{gd2}}$
 - $C_{gd1} = C_{ox}X_{dM1}W_{M1}$
 - 米勒效应



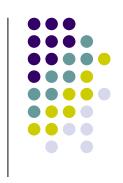


- CMOS反相器寄生电容
 - 扩散电容C_{db1}和C_{db2}
 - 扩散电容是高度非线性的,通常对其线性化处理

$$C_{eq} = K_{eq} C_{j0}$$

$$K_{eq} = \frac{-\phi_0^m}{(V_{high} - V_{low})(1-m)} \left[(\phi_0 - V_{high})^{1-m} - (\phi_0 - V_{low})^{1-m} \right]$$

- 连线电容C_w
 - 与连线的长度和宽度及扇出的数目有关



- CMOS反相器寄生电容
 - 扇出的栅电容Cg3和Cg4
 - 由负载门M₃和M₄的栅电容构成

$$\begin{split} C_{\textit{fan-out}} &= C_{\textit{gate}}(\textit{NMOS}) + C_{\textit{gate}}(\textit{PMOS}) \\ &= (C_{\textit{GSOn}} + C_{\textit{GDOn}} + W_{\textit{n}}L_{\textit{n}}C_{\textit{ox}}) + (C_{\textit{GSOp}} + C_{\textit{GDOp}} + W_{\textit{p}}L_{\textit{p}}C_{\textit{ox}}) \end{split}$$

- 表达式简化
 - 假设栅电容的所有部分都连在V_{out}和GND(或V_{DD})之间, 并且忽略了栅漏电容上的米勒效应
 - 近似认为所连接的门的沟道电容在关注时间内保持不变为WLC_{ox}



- 传播延时: 一阶分析
 - 传播延时t_p=RC

$$t_p = \int_{v_1}^{v_2} \frac{C_L(v)}{i(v)} dv$$

$$R_{eq} = \frac{1}{-V_{DD}/2} \int_{V_{DD}}^{V_{DD}/2} \frac{V}{I_{DSAT}(1+\lambda V)} dV \approx \frac{3}{4} \frac{V_{DD}}{I_{DSAT}} (1 - \frac{7}{9} \lambda V_{DD})$$

$$\sharp \psi \quad I_{DSAT} = k' \frac{W}{L} \left((V_{DD} - V_T) V_{DSAT} - \frac{V_{DSAT}^{2}}{2} \right)$$

$$t_{pHL} = \ln(2) R_{eqn} C_{L} = 0.69 R_{eqn} C_{L}$$

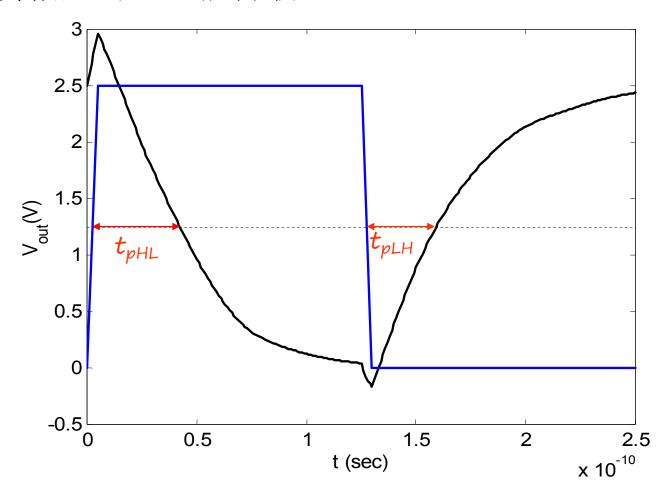
$$t_{pLH} = \ln(2) R_{eqp} C_{L} = 0.69 R_{eqp} C_{L}$$

$$t_{p} = \frac{t_{pHL} + t_{pLH}}{2} = 0.69 C_{L} \left(\frac{R_{eqn} + R_{eqp}}{2}\right)$$





• 传播延时: 一阶分析



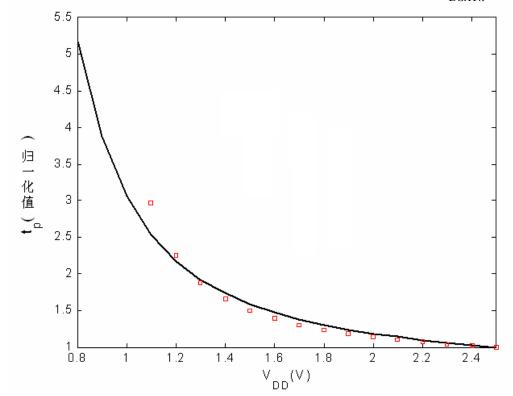


- 减少CMOS门传播延时的设计技术
 - 减少C_I
 - 使门本身的内部扩散电容、互连线电容和扇出电容减少
 - 增加晶体管的W/L比
 - 减少电阻负载,但反过来会增加电容,称为自载效应
 - 较宽的晶体管具有较大的栅电容,增加了驱动门的扇出系数
 - 提高V_{DD}



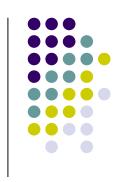


- 减少CMOS门传播延时的设计技术
 - 电源电压 V_{DD} 对延时的影响 忽略沟道调制系数 $\lambda t_{pHL} = 0.69 \frac{3}{4} \frac{C_L V_{DD}}{I_{DSATn}} = 0.52 \frac{C_L V_{DD}}{(W/L)_n k'_n V_{DSATn} (V_{DD} - V_{Tn} - V_{DSATn}/2)}$



如果
$$V_{DD}$$
 \Box $V_{Tn} - V_{DSATn} / 2$

$$t_{pHL} = 0.52 \frac{C_L}{(W/L)_n k_n' V_{DSATn}}$$



- 从设计角度考虑延时
 - NMOS与PMOS比

$$C_{L} = (C_{dp1} + C_{dn1}) + (C_{gp2} + C_{gn2}) + C_{W}$$

$$\beta = (W/L)_{p} / (W/L)_{n} \quad C_{dp1} \approx \beta C_{dn1} \quad C_{L} = (1+\beta)(C_{dn1} + C_{gn2}) + C_{W}$$

$$t_{p} = \frac{0.69}{2} \left((1+\beta)(C_{dn1} + C_{gn2}) + C_{W} \right) \left(R_{eqn} + \frac{R_{eqp}}{\beta} \right) \qquad r = \frac{R_{eqp}}{R_{eqn}}$$

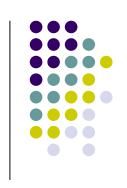
$$= 0.345 \left((1+\beta)(C_{dn1} + C_{gn2}) + C_{W} \right) R_{eqn} \left(1 + \frac{r}{\beta} \right)$$

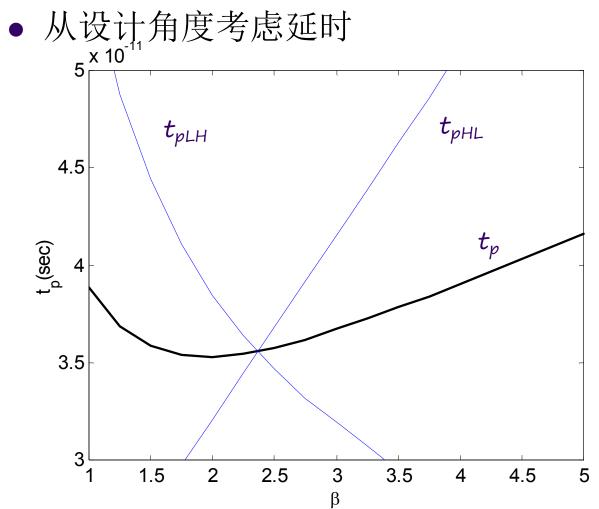
$$\frac{\partial t_{p}}{\partial \beta} = 0.345 R_{eqn} \left[\left(C_{dn1} + C_{gn2} \right) \left(1 + \frac{r}{\beta} \right) - \left((1+\beta)(C_{dn1} + C_{gn2}) + C_{W} \right) \frac{r}{\beta^{2}} \right] = 0$$

$$(\beta^{2} + r\beta) = \left((1+\beta) + \frac{C_{W}}{(C_{dn1} + C_{gn2})} \right) r$$

$$\beta^{2} = r \left(1 + \frac{C_{W}}{(C_{dn1} + C_{gn2})} \right) \beta_{opt} = \sqrt{r \left(1 + \frac{C_{W}}{(C_{dn1} + C_{gn2})} \right)}$$







$$\beta = W_p/W_n$$

$$\beta_{opt} = \sqrt{r \left(1 + \frac{C_W}{(C_{dn1} + C_{gn2})}\right)}$$



- 考虑性能时反向器尺寸的确定
 - 负载电容可以分为本征和外部电容两部分
 - 本征电容Cint: 扩散电容和栅漏覆盖电容
 - 外部电容C_{ext}: 扇出和导线电容

$$C_{L} = C_{\text{int}} + C_{\text{ext}}$$

$$t_{p} = 0.69 \, \text{R}_{\text{eq}} (C_{\text{int}} + C_{\text{ext}})$$

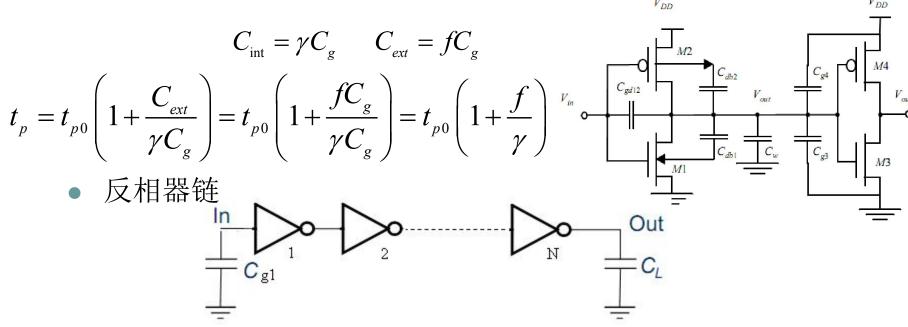
$$= 0.69 \, \text{R}_{\text{eq}} \, C_{\text{int}} (1 + C_{\text{ext}} / C_{\text{int}}) = t_{p0} (1 + C_{\text{ext}} / C_{\text{int}})$$
 弓 入尺寸系数S $C_{\text{int}} = SC_{\text{iref}} \, \text{R}_{\text{eq}} = R_{\text{ref}} / S$
$$t_{p} = 0.69 \, \text{R}_{\text{ref}} / S) (SC_{\text{iref}}) (1 + C_{\text{ext}} / SC_{\text{iref}})$$

$$= 0.69 \, \text{R}_{\text{ref}} \, C_{\text{iref}} (1 + C_{\text{ext}} / SC_{\text{iref}}) = t_{p0} (1 + C_{\text{ext}} / SC_{\text{iref}})$$

- 从上式可以得出两个重要的结论
 - 反相器的本征延时t_{p0}与门的尺寸无关
 - 使S无穷大可使性能最大可能的得到改善

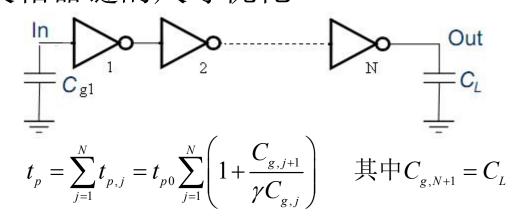


- 反相器链的尺寸优化
 - 反相器的输入电容 C_g 与本征输出电容之间的关系



$$t_{p,j} = t_{p0} \left(1 + \frac{C_{g,j+1}}{\gamma C_{g,j}} \right) = t_{p0} \left(1 + \frac{f_j}{\gamma} \right)$$

• 反相器链的尺寸优化



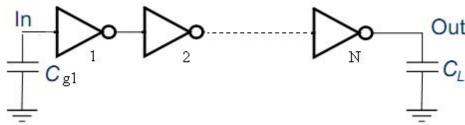
求 t_p 关于 $C_{g,j}$ 的导数可得最小延时的约束条件 $C_{g,j+1}/C_{g,j}=C_{g,j}/C_{g,j-1}$ 其中(j=2...N)

$$C_{g,j} = \sqrt{C_{g,j-1}C_{g,j+1}}$$

每个反相器有相同的等效扇出 $f = f_j = C_{g,j} / C_{g,j-1}$ 给定 $C_{g,1}$ 和 C_L ,可得尺寸系数 $f = \sqrt[N]{C_L / C_{g,1}}$ 因此反相器链的最小延时: $t_p = Nt_{p0}(1 + \sqrt[N]{F} / \gamma)$



• 反相器链的正确级数



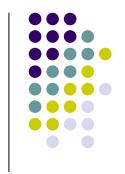
$$t_p = Nt_{p0} (1 + \sqrt[N]{F} / \gamma)$$

求 t_p 关于级数N的导数可得最优解

$$\gamma + \sqrt[N]{F} - \frac{\sqrt[N]{F} \ln F}{N} = 0$$

$$f = e^{(1+\gamma/f)}$$

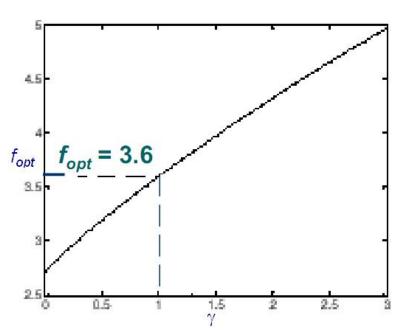
上式只有一个收敛解 $\gamma = 0$ 此时忽略自载

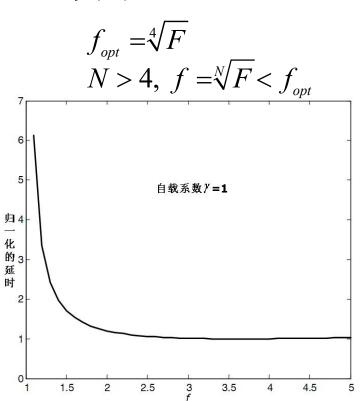






• 反相器链的正确级数





不同驱动器结构的t_{opt}/t_{p0}与F的关系

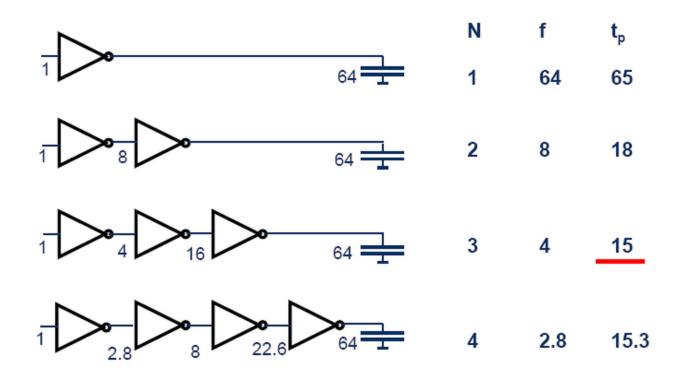
	ορι ρο		
F	无缓冲器	两级反相器	反相器链
10	11	8.3	8.3
100	101	22	16.5
1000	1001	65	24.8
10,000	10,001	202	33.1





• 反相器链的正确级数

$$t_p = Nt_{p0}(1 + \sqrt[N]{F} / \gamma)$$

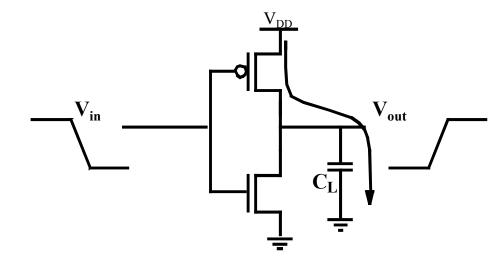




- CMOS反相器的功耗包括
 - 动态功耗
 - 充放电电容
 - 短路电流
 - 静态功耗
 - 漏电电流

延时

• 动态功耗



能量/翻转 $C_L V_{DD}^2$

功率=能量/翻转×频率= $C_L V_{DD}^2 f_{0\rightarrow 1}$

- 从上式可以看出
 - 动态(翻转)的能量和功耗与驱动器件的电阻无关
 - 为减少功耗需要减少 C_L , V_{DD} , $f_{0\rightarrow 1}$





n

Out

• 为减少能耗的尺寸优化

$$C_{g1}$$
 1

(

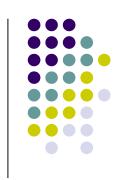
$$t_{p} = t_{p0} \left(\left(1 + \frac{f}{\gamma} \right) + \left(1 + \frac{F}{f \gamma} \right) \right)$$

$$t_{pHL} = 0.69 \frac{3}{4} \frac{C_L V_{DD}}{I_{DSATn}} = 0.52 \frac{C_L V_{DD}}{(W/L)_n k'_n V_{DSATn} (V_{DD} - V_{Tn} - V_{DSATn}/2)}$$

$$t_{p0} \Box \frac{V_{DD}}{V_{DD} - V_{T} - V_{DSAT}/2}$$

$$C_{L} = Cg1 + (\gamma Cg1 + fCg1) + (f\gamma Cg1 + FCg1) = Cg1((1+\gamma)(1+f) + F)$$

$$E = V_{DD}^{2}Cg1((1+\gamma)(1+f) + F)$$



• 为减少能耗的尺寸优化

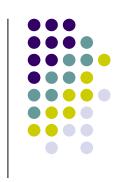
Out
$$t_{p} = t_{p0} \left(\left(1 + \frac{f}{\gamma} \right) + \left(1 + \frac{F}{f \gamma} \right) \right)$$

$$C_{ext}$$

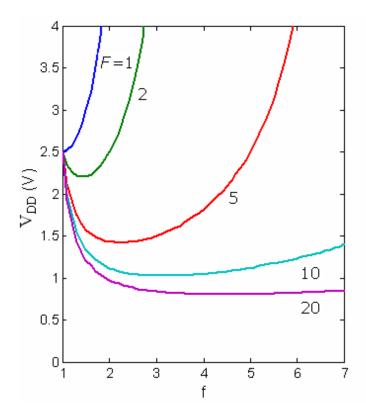
• 性能约束就是指尺寸放大电路的传播延时应当等于或小于参 考电路(f=1, V_{dd}=V_{ref})的延时

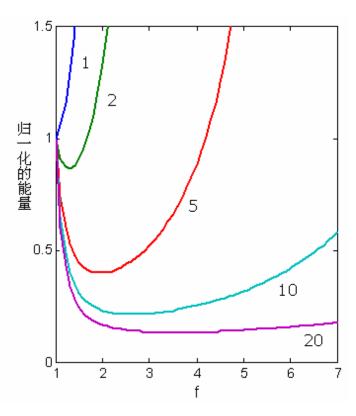
$$\frac{t_{p}}{t_{pref}} = \frac{t_{p0} \left(2 + f + \frac{F}{f}\right)}{t_{p0ref} \left(3 + F\right)} = \left(\frac{V_{DD}}{V_{ref}}\right) \left(\frac{V_{ref} - V_{TE}}{V_{DD} - V_{TE}}\right) \left(\frac{2 + f + \frac{F}{f}}{3 + F}\right) = 1$$

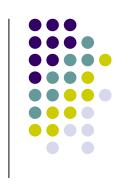
$$\frac{E}{E_{ref}} = \left(\frac{V_{DD}}{V_{ref}}\right)^{2} \left(\frac{2 + 2f + F}{4 + F}\right)$$



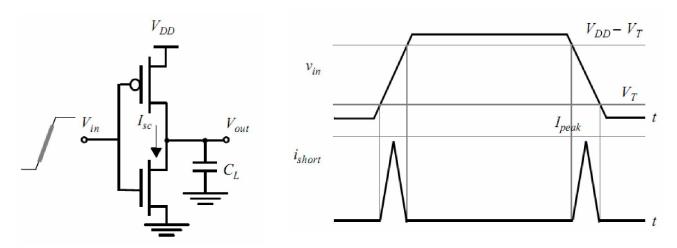
- 为减少能耗的尺寸优化
 - 改变器件尺寸并降低电源电压时减小逻辑电路能好的有效办法
 - 在最优值之外过多加大晶体管尺寸会消耗更多能量





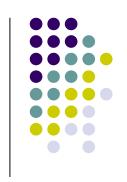


- 直接通路电流引起的功耗
 - 输入信号的逐渐变化造成了开关过程中V_{DD}和GND之间在短期内 出现一条直流通路,此时NMOS和PMOS管同时导通

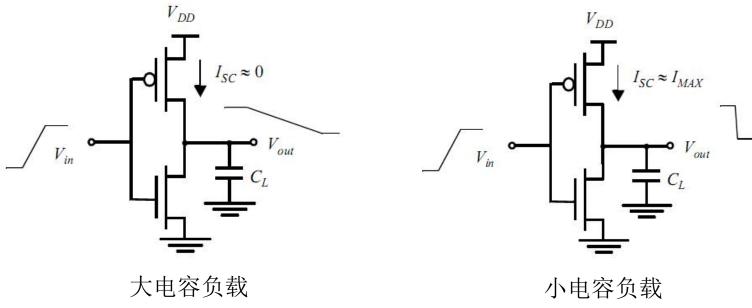


$$E_{dp} = V_{DD} \frac{I_{peak} t_{sc}}{2} + V_{DD} \frac{I_{peak} t_{sc}}{2} = V_{DD} I_{peak} t_{sc}$$

$$P_{dp} = V_{DD} I_{peak} t_{sc} f = C_{sc} V_{DD}^{2} f$$

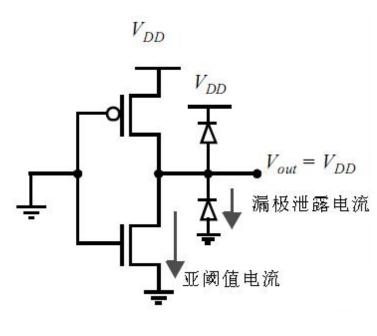


- 直接通路电流引起的功耗
 - 峰值短路电流
 - 取决于器件的饱和电流,因此与器件的尺寸有关
 - 降低电源电压可以减少短路电流
 - 与输入输出的斜率比有关





- 静态功耗
 - 峰值短路电流(漏电流功耗)



$$P_{\rm stat} = I_{\rm stat} V_{\rm DD}$$



- 综合考虑
 - 总功耗

$$P_{tot} = P_{dyn} + P_{dp} + P_{stat} = \left(C_L V_{DD}^2 + V_{DD} I_{peak} t_s\right) f_{0 \to 1} + V_{DD} I_{leak}$$

• 功耗-延时积或每操作的能量损耗

$$PDP = P_{av}t_{p}$$

$$PDP = C_{L}V_{DD}^{2}f_{\max}t_{p} = \frac{C_{L}V_{DD}^{2}}{2}$$

• 能量-延时积

$$EDP = PDP \times t_p = P_{av}t_p^2 = \frac{C_L V_{DD}^2}{2}t_p$$